

PATENT ABSTRACTS OF JAPAN

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H01L 21/027(21)Application number : **10-272570**(71)Applicant : **CANON INC**(22)Date of filing : **09.09.1998**(72)Inventor : **MURAKAMI EIICHI****(54) RETICLE AND PROJECTION ALIGNER**

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a reticle usable even if an exposure wavelength is as short as 157 nm of an F2 laser and an aligner using the reticle.

SOLUTION: A fluoride crystal material is used as the reticle material and the directions of one crystal axis of the crystal and at least one of the X-, Y- and Z-axes of the projection aligner are aligned or are perpendicular. The fluoride crystal material is preferably CaF2 or MgF2 or LiF.

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